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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/646,543	08/21/2003	Stefan Braun	SPM-365-A	9852	
ANDREW R. I	7590 01/10/200 BASIL	EXAMINER			
Young & Basil Suite 624	e, P.C.	LUND, JEFFRIE ROBERT			
3001 West Big	Beaver Road	ART UNIT	PAPER NUMBER		
Troy, MI 4808	4	1763			
SHORTENED STATUTORY PERIOD OF RESPONSE		MAIL DATE	DELIVERY MODE		
3 MO	NTHS	01/10/2007	PAPER		

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

			Application	No.	Applicant(s)				
Office Action Summary		10/646,543		BRAUN ET AL.					
		Examiner		Art Unit					
			Jeffrie R. Lu		1763				
Period fo	The MAILING DATE of this commun or Reply	nication app	ears on the d	cover sheet with the c	orrespondence ac	ldress			
WHIC - External after - If NC - Failu . Any	ORTENED STATUTORY PERIOD FOR CHEVER IS LONGER, FROM THE MINISTRANCE IS LONGER, FROM THE MINISTRANCE IS LONGER, FROM THE MINISTRANCE IS LONGER AND THE MONTHS from the mailing date of this composition of the properties of the maximum is the toreply within the set or extended period for replication of the properties of the maximum is the properties of the maximum in the set or extended period for replication of the maximum in the set or extended period for replication of the maximum in the set or extended period for replication of the maximum in the maximum	MAILING DA s of 37 CFR 1.13 munication. tatutory period w y will, by statute,	ATE OF THIS 36(a). In no even vill apply and will a cause the applica	S COMMUNICATION I, however, may a reply be time expire SIX (6) MONTHS from ation to become ABANDONE	N. nely filed the mailing date of this of 0 (35 U.S.C. § 133).				
Status					•	•			
1)⊠	Responsive to communication(s) file	ed on <i>11 M:</i>	av 2006						
	Responsive to communication(s) filed on <u>11 May 2006</u> . This action is FINAL . 2b)⊠ This action is non-final.								
/	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is								
-/	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Dienoeiti	on of Claims			,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,					
· _									
	Claim(s) <u>1-8,10-12 and 15-23</u> is/are pending in the application.								
	4a) Of the above claim(s) 8,10 and 16-23 is/are withdrawn from consideration.								
· —	5) Claim(s) is/are allowed.								
	S)⊠ Claim(s) <u>1-7, 10-12 and 15</u> is/are rejected.								
	Claim(s) is/are objected to.								
8)[_]	8) Claim(s) are subject to restriction and/or election requirement.								
Applicati	on Papers				•				
9)[The specification is objected to by the	ne Examiner	r.						
10)⊠	The drawing(s) filed on 21 August 20	003 is/are:	a) accept	ed or b)□ objected t	o by the Examine	er.			
	10) The drawing(s) filed on <u>21 August 2003</u> is/are: a) accepted or b) objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).								
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).								
11)[11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.								
Priority u	ınder 35 U.S.C. § 119								
12)⊠ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a)⊠ All b)□ Some * c)□ None of:									
	1.⊠ Certified copies of the priority documents have been received.								
	2. Certified copies of the priority documents have been received in Application No								
	3. Copies of the certified copies of the priority documents have been received in this National Stage								
	application from the International Bureau (PCT Rule 17.2(a)).								
* See the attached detailed Office action for a list of the certified copies not received.									
Attachment	• •			\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	(DTO 440)				
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (F	PTO-948\	4) Interview Summary Paper No(s)/Mail Da					
_	nation Disclosure Statement(s) (PTO-1449 or) 🔲 Notice of Informal Pa		D-152)			
Paper No(s)/Mail Date 6) Other:									

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1-7, 11, 12, and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ito, JP 60-181264, in view of Mori et al, US Patent Application Publication 2002/0187265 A1, and Baldwin et al, US Patent Application Publication 2002/0131182 A1.

Ito teaches a linearly oscillating mask (figure 1d) having a ratio of free crosssections of the perforations being discretely present in the mask and the intermediate web surface that varies over the total surface, and the respective distance of the substrate surface, and rotating the substrate. (Abstract, figures)

Ito differs from the present invention in that Ito does not teach rotating the mask and the substrate together with respect of the plasma source by rotation of both the substrate and the mask about a common axis of rotation, or a magnetron sputtering source.

Mori et al teaches rotating the mask and the substrate together with respect of the plasma source by rotation of both the substrate 1 and the mask 200 about a common axis of rotation. (Figure 18)

Baldwin et al teaches a Magnetron sputtering source 18.

Application/Control Number: 10/646,543

Art Unit: 1763

The motivation for rotating the mask of Ito is to provide a more uniform distribution of material to the surface of the mask and substrate.

The motivation for replacing the evaporation source of Ito with a magnetron sputtering source is to provide an alternate and equivalent coating material source.

Therefore it would have been obvious to one of ordinary skill in the art at the time the invention was made to rotate the mask and replace the evaporation source with a magnetron sputtering source.

Response to Arguments

3. Applicant's arguments with respect to claims 1-7, 11, 12, and 15 have been considered but are most in view of the new ground(s) of rejection.

Conclusion

- 4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The cited art teaches the technological background of the invention.
- 5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jeffrie R. Lund whose telephone number is (571) 272-1437. The examiner can normally be reached on Monday-Thursday (6:30 am-6:00pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the

Art Unit: 1763

Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jeffrie R. Lund Primary Examiner Art Unit 1763

JRL 1/8/07